hõnle group





UVAPRINT LE

Circumferential UV light system

System-Features

- Closed elliptical reflector
- Production speed up to 3.000 m/min
- High-intensity circumferential irradiation

Advantages

- Low maintenance
- Shutter system prevents excessive heating of the irradiated object during production interruptions

UVAPRINT LE – circumferental UV light system

UVAPRINT LE is a high intensity UV lamp unit for uniform circumferential irradiation of filamentary materials.

The system incorporates a reflector system which produces a focused line of UV light at the central axis of a quartz tube. This concentrates the emitted energy, resulting in an extremely high intensity and maximum performance.

The lamp housing can be swung open and is therefore easy to maintain.

The shown version shows a unit with two lamps in one housing. Both lamps are ignited and controlled independently from each other. This allows a maximum of production flexibility.

UVAPRINT LE is particularly suitable for curing of inks and coatings on all types of filament materials. Typical examples include: Optical Fibre, Cable, Wire and Plastic Thread.

Principle

Two reflectors are installed opposite each other to produce an ellipse. The lamp is mounted in the focal point of the first reflector which produces a focused line of high



intensity UV light at the focal point of the second reflector. Inert gas shielding can be installed as required.

Technical Data

UVAPRINT LE is fitted with a shutter system to protect the filament material from over exposure during production interruptions.

UVAPRINT LE is available in 100 mm to 500 mm arc length with a maximum power up to 12 kW (240 W/cm). The unit is also available with two lamps in one housing. The power supply is an electronical ballast working with a main voltage of 400 V - 480 V/ 3 Phases and 50 Hz or 60 Hz.





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